

11/21/03

**ELECTRONIC INFORMATION DISCLOSURE STATEMENT**

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	Interconnect Structure Diffusion Barrier with High Nitrogen Content						
<p>Application Number :</p> <p>Confirmation Number:</p> <p>First Named Applicant: Cyril Cabral</p> <p>Attorney Docket Number: FIS920030252US1</p> <p>Art Unit:</p> <p>Examiner:</p> <p>Search string: ( 6346745 or 6491978 or 6117769 or 20010041250 or 20020030222 or 20030032281 ).pn</p>							
<b>US Patent Documents</b>							
<b>Note: Applicant is not required to submit a paper copy of cited US Patent Documents</b>							
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
KR	1	6346745	2002-02-12	NOGAMI, ET AL.			
I	2	6491978	2002-12-10	KALYANAM			
KR	3	6117769	2000-09-12	NOGAMI, ET AL.			
<b>US Published Applications</b>							
<b>Note: Applicant is not required to submit a paper copy of cited US Published Applications</b>							
init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
KR	1	20010041250	2001-11-15	WERKHOVEN, ET AL.			
I	2	20020030222	2002-03-14	AGARWAL			
KR	3	20030032281	2003-02-13	WERKHOVEN, ET AL.			
<b>Signature</b>							
Examiner Name				Date			
[Signature]				6/2/05			